



## NOTICE OF GROUND OF REJECTION

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Applicant: Mitsubishi Denki Kabushiki Kaisha, etc.  
Attorney: Kim & Chang  
Pat. Appln. No.: 10-2000-0019953  
Title of the Invention: Method of And Apparatus for Washing Photomask  
And Washing Solution for Photomask

It is noticed that the present application is rejected under the provision of Article 63 of the Patent Law.

### [Ground]

The invention of the subject application cited in claims 1-3 could have been readily invented, before filing thereof, by a person having ordinary skills in the technical field to which the present invention belongs, from the teachings set forth in the following remarks. Therefore, a patent cannot be granted thereto under the provision of Article 29, Paragraph 2 of the Patent Law.

### [Remarks]

Claims 1 to 3 of the present application relates to a method of washing comprising the first step of removing organic matter and metal impurities present on the surface of a photo mask, the second step of removing foreign matter with H<sub>2</sub> gas dissolved water, and the third step of drying, as well as to a washing solution containing H<sub>2</sub> gas dissolved water. The invention according to these claims, however, could have been readily made from Japanese Patent Laying-Open No. 11-29794 (laid-open on 1999, 2,2: Reference 1) describing an RCA washing method in which hydrogen gas is supplied as washing water for washing electronic material contaminated with fine particles, and the washing water is irradiated with supersonic waves to remove metal components, Japanese Patent Laying-Open No. 11-7892 (laid-open on 1999, 1,12: Reference 2) describing method and apparatus for washing, in which after precipitation in a washing tank, foreign matters are removed by external supersonic waves, followed by rinsing and drying, and from Japanese Patent Laying-Open No. 10-317182 (laid-open on 1998, 12, 2: Reference 3) describing a washing apparatus in which chloride, fluorine based solvent and chloride ions are removed.

[Attachment] Japanese Patent Laying-Open No. 11-29794  
Japanese Patent Laying-Open No. 11-7892  
Japanese Patent Laying-Open No. 10-317182

April 25, 2002